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(71) Applicant (for all designated States except US): **TOKYO OHKA KOGYO CO., LTD.** [JP/JP]; 150, Nakamaruko, Nakahara-ku, Kawasaki-shi, Kanagawa 211-0012 (JP).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **MASUDA, Yasuo** [JP/JP]; c/o Tokyo Ohka Lpgyo Co., Ltd., 150, Nakamaruko, Nakahara-ku, Kawasaki-shi, Kanagawa, 211-0012 (JP). **OKUI, Toshiaki** [JP/JP]; c/o Tokyo Ohka Kogyo Co., Ltd., 150, Nakamaruko, Nakahara-ku, Kawasaki-shi, Kanagawa, 211-0012 (JP).

(74) Agents: **TANAI, Sumio et al.**; 2-3-1, Yaesu, Chuo-ku, Tokyo 104-8453 (JP).

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(54) Title: POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN FORMATION

(57) Abstract: A means for increasing development velocity of a positive photoresist composition is provided which contains a photosensitive novolak resin formed by replacing some hydrogen atoms within those of all phenolic hydroxyl groups of alkali soluble novolak resin by 1,2-naphthoquinonediazide sulfonyl group. This means is positive photoresist composition and a formation method of a resist pattern using the composition which contains (A) a photosensitive novolak resin formed by replacing some hydrogen atoms within those of all phenolic hydroxyl groups of alkali soluble novolak resin by 1,2-naphthoquinonediazide sulfonyl group, which is dissolved in (B) propylene glycol alkyl ether acetate.